

Figure 1. Schematic of thermal Ni ALE surface chemistry based on sequential exposures to SO_2Cl_2 and PMe_3 .

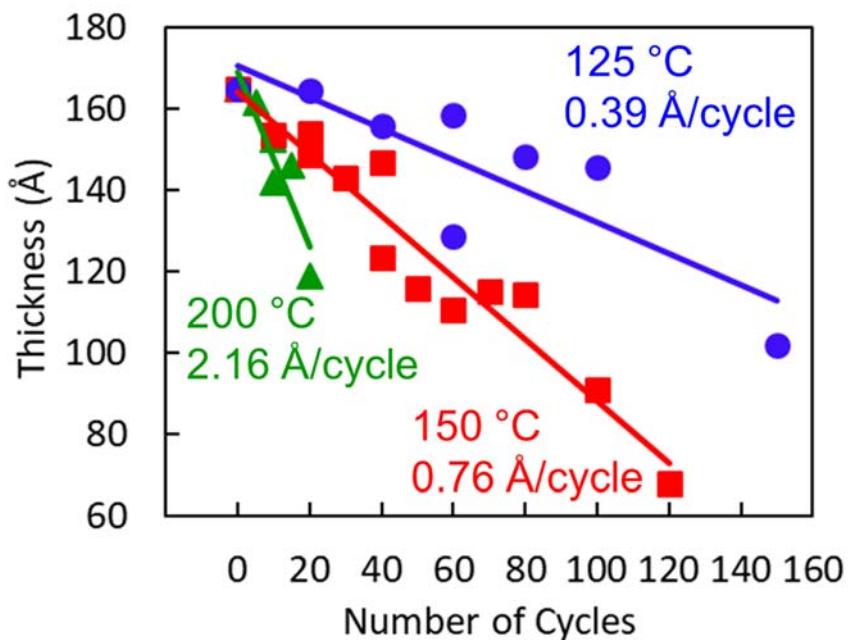


Figure 2. XRR measurements of nickel film thickness versus number of Ni ALE cycles at 125 °C, 150 °C and 200 °C using SO_2Cl_2 and PMe_3 as the reactants.